

ABSTRACT OF THE DISCLOSURE

5 Provided herein is a method for cleaning a process
chamber for semiconductor and/or flat panel display
manufacturing. This method comprises the steps of converting a
non-cleaning feed gas to a cleaning gas in a remote location and
then delivering the cleaning gas to the process chamber for
cleaning. Such method may further comprise the step of
10 activating the cleaning gas outside the chamber before the
delivery of the gas to the chamber. Also provided is a method of
eliminating non-cleaning feed gas from the cleaning gas by cryo
condensation.

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